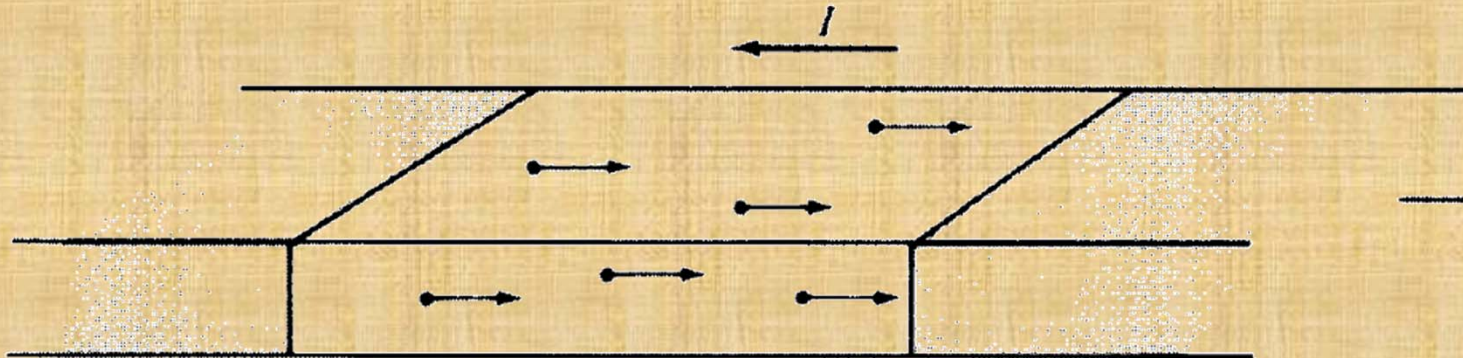


# Conduction

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# Conduction

- Transit Time



- Current

$$I = -\frac{|Q|}{\tau}$$





# Conduction...

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- Drift
  - Random process
  - In presence of external field
  - Complicated Movement – Scattering Mechanisms
    - Lattice Vibration
    - Ionized Impurities
- Average velocity -- Drift Velocity :  $v_d$ 
  - Semiconductor Material
  - Doping type/concentration
  - Temperature
  - Carrier type
  - Applied electric field





# Conduction

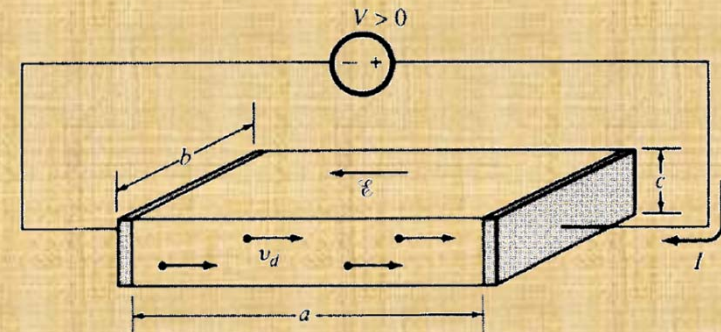
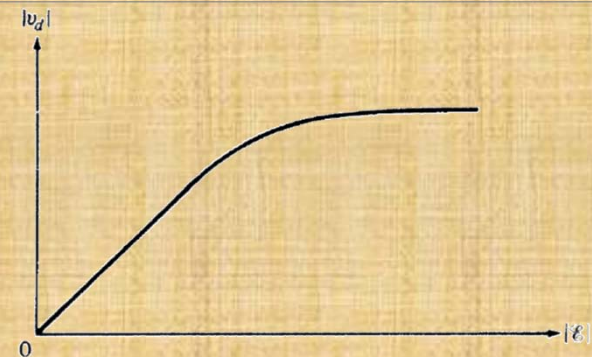
- Velocity Saturation
- In following figure we assume it n-type semiconductor
- If the electron velocity saturated then its move with constant velocity

- Electron transit time :  $\tau = \frac{a}{v_d}$
- The magnitude  $|Q|$  of the total free electron charge found inside the bar at a given time instant is :

$$|Q| = nq(abc)$$

- Therefore Current becomes:

$$I = \frac{nq(abc)}{\tau}$$
$$I = nq(bc)v_d$$





# Conduction...

- magnitude of the charge per unit area:  $|Q'| = \frac{|Q|}{ab}$   
 $I = b|Q'|v_d$

- The Case of Low Electric Fields

- For such fields,  $v_d$  is proportional to  $E$  – Mobility parameter:  $\mu_B$

$$v_d = \mu_B \times E$$

$$E = \frac{V}{a}$$

$$I = \mu_B b/a |Q'|V$$

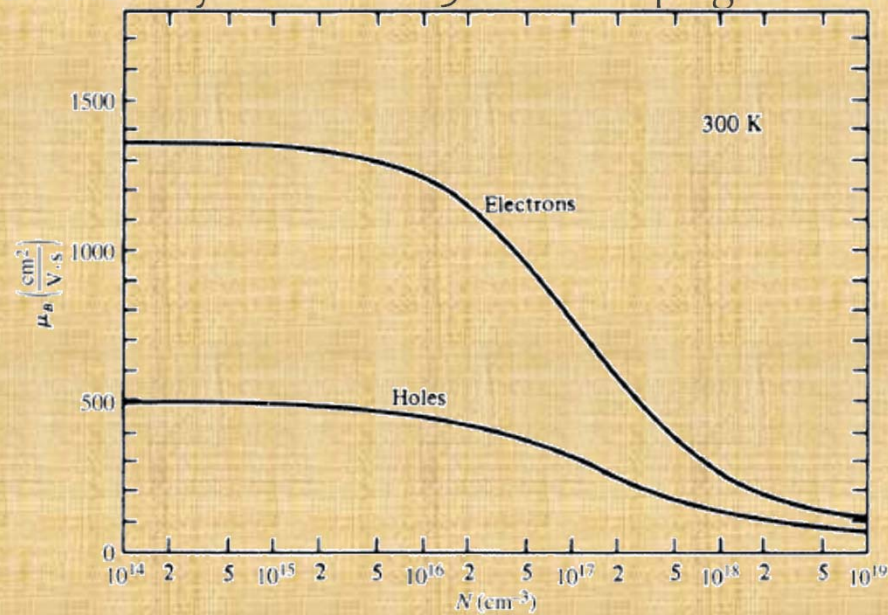
- Independent of  $c$ , bar thickness
    - The drift current is proportional to the voltage (Ohm's Law)
    - Transit time :  $\tau = a^2/\mu_B V$  – Dependency to  $a^2$ 
      - The distance of electrons must travel becomes larger
      - the magnitude of the electric field becomes smaller





# Conduction...

- Electron and hole bulk mobility in silicon at 300 K vs doping concentration





# Conduction...

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- Conductance and Conductivity

$$I = \mu_B nqVbc/a$$
$$I = GV$$

- Conductance:  $G = \frac{\sigma bc}{a} = \mu_B |Q'| b/a$ , Conductivity:  $\sigma = \mu_B nq$

- The inverse of the conductivity, called the *resistivity*, is also used.

- The resistance of the bar  $R = 1/G$  is

$$R = R_s a/b$$

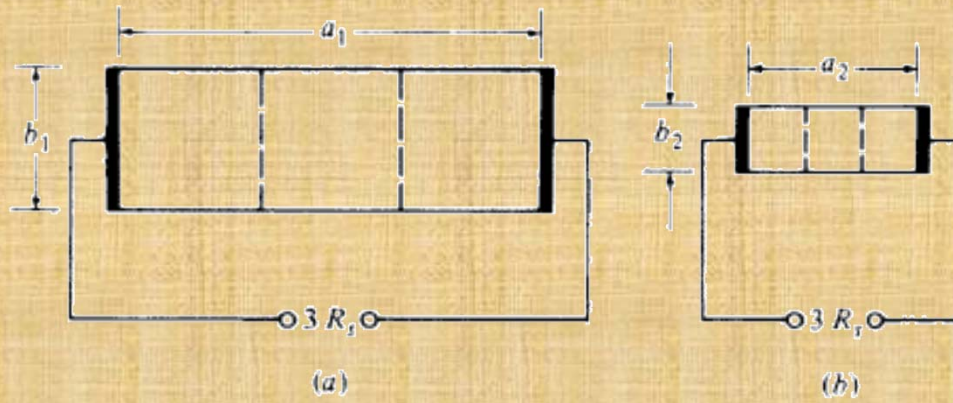
- Sheet resistance:  $R_s = (\mu_B |Q'|)^{-1}$

- If  $a=b$ :  $R_s=R$ , Resistance per squares.  $R$  will be given by  $R_s$ , times the number of squares in the path of the current.





# Conduction...



Results analogous to the ones in this section can be given in the case of hole conduction.





# Conduction...

## ■ Diffusion

- Reason: Concentration Gradient
- Random motion of the particles tends to make them spread out from regions of high concentration to regions of low concentration

■ Fick's Law

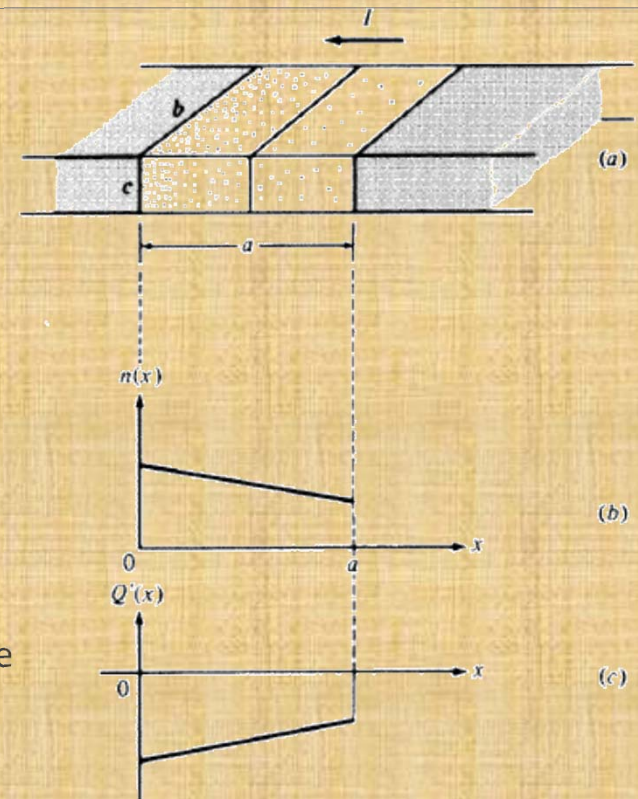
■ Current:

$$I = Dq(bc)(-dn/dx)$$

- D is Diffusion Constant
- Diffusion and Mobility : Einstein relationship

$$D = \mu_B \phi_T$$

- Same equation for hole , the only difference is current positive





# Conduction...

- Current in steady state : Diffusion and drift relation
- Electron charge in slice of  $\Delta x$  :  $Q = (-q)n(x)bc\Delta x$
- Charge per unit area :  $Q' = \frac{Q}{b\Delta x} = (-q)cn(x)$
- Current :  $I = \mu_B\phi_T b \frac{dQ'(x)}{dx}$
- If the plot is straight line

$$\frac{dQ'(x)}{dx} = \frac{Q'(a) - Q'(0)}{a}$$

$$I = \mu_B\phi_T \frac{b}{a} (Q'(a) - Q'(0))$$

- The total charge  $Q = ab \frac{Q'(a) + Q'(0)}{2}$  and therefore the transit time:  $\tau = \frac{a^2}{\mu_B(2\phi_T)} \frac{Q'(0) + Q'(a)}{Q'(0) - Q'(a)}$





# Conduction...

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- For perfect sink:  $Q'(a) = 0$

$$\tau = \frac{a^2}{\mu_B(2\phi_T)}$$

- It is very similar to drift transit time
- in contrast to the drift case, where  $\tau$  can be made small by applying a large  $V$ , here  $\tau$  is fixed at a comparatively large value, due to the fixed, small value  $2\phi_T$





# Conduction

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- Total current: Contribution of both electron and hole. Also Both drift and diffusion mechanism include in it.
- Four possible current components:
  - Electron
    - Drift
    - Diffusion
  - Hole
    - Drift
    - Diffusion
- In thermal equilibrium implies zero electron current *and* zero hole current.

